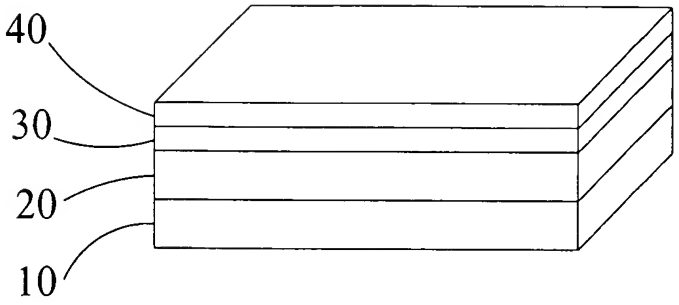
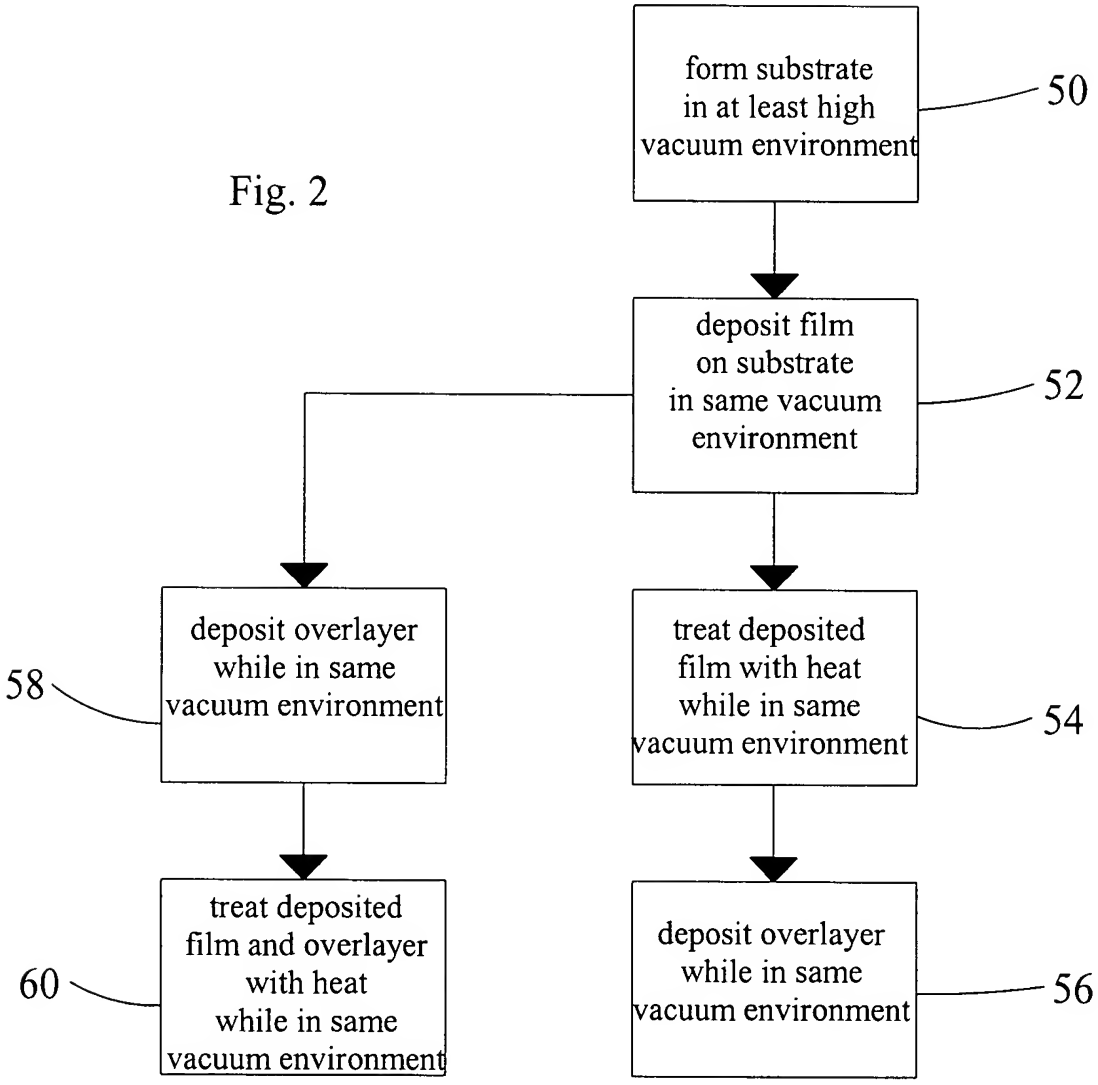

40
30
20
10

Fig. 1

Fig. 2


form substrate in at least high vacuum environment
50
deposit film on substrate in same vacuum environment
52
deposit overlayer while in same vacuum environment
58
treat deposited film with heat while in same vacuum environment
54
treat deposited film and overlayer with heat while in same vacuum environment
60
deposit overlayer while in same vacuum environment
56